

East 8 USPB, USPT, WPID, JPO

L Number	Hits	Search Text	DB	Time stamp
1	2257002	etch\$ or patern\$ or remov\$	USPAT; US-PGPUB	2004/09/27 14:38
2	320983	poly or polysi or polysilicon or polycrystal\$	USPAT; US-PGPUB	2004/09/27 14:39
3	555024	"o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3"	USPAT; US-PGPUB	2004/09/27 14:39
4	780283	oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide	USPAT; US-PGPUB	2004/09/27 14:39
5	342723	plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion)	USPAT; US-PGPUB	2004/09/27 14:40
6	42518	(etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)	USPAT; US-PGPUB	2004/09/27 13:22
7	1739	((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))	USPAT; US-PGPUB	2004/09/27 13:22
8	158053	oe or me or overetch\$ or (over with etch\$) or (main with etch\$)	USPAT; US-PGPUB	2004/09/27 14:43
9	0	"o.e." or "m.e."	USPAT; US-PGPUB	2004/09/27 14:40
10	3605060	1st or first or (etch\$ or patern\$ or remov\$) st	USPAT; US-PGPUB	2004/09/27 14:40
11	3023301	2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second	USPAT; US-PGPUB	2004/09/27 14:41
12	341513	((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$))	USPAT; US-PGPUB	2004/09/27 13:29
13	1739	((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion)) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$))))	USPAT; US-PGPUB	2004/09/27 13:31
14	683313	(1st or first or (etch\$ or patern\$ or remov\$) st) with step	USPAT; US-PGPUB	2004/09/27 13:34
15	416824	(2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step	USPAT; US-PGPUB	2004/09/27 13:36
16	243140	((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)	USPAT; US-PGPUB	2004/09/27 13:36
17	42390	((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$)	USPAT; US-PGPUB	2004/09/27 13:36
18	42390	((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$))	USPAT; US-PGPUB	2004/09/27 13:37

19	180	(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$))))	USPAT; US-PGPUB	2004/09/27 13:37
20	13038	(dual or two) with step with (etch\$ or patern\$ or remov\$)	USPAT; US-PGPUB	2004/09/27 13:38
21	15	(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$))	USPAT; US-PGPUB USPAT; US-PGPUB	2004/09/27 13:38
22	65	(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$)	USPAT; US-PGPUB	2004/09/27 13:38
23	318	(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((over with etch\$) or (main with etch\$))	USPAT; US-PGPUB	2004/09/27 13:40

24	479	<p>((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$) ) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((over with etch\$) or (main with etch\$))))</p>	USPAT; US-PGPUB	2004/09/27 13:45
25	319926	<p>cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide)</p>	USPAT; US-PGPUB	2004/09/27 14:41

26	201	<p>((((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$) ) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((over with etch\$) or (main with etch\$)))) same (cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide))</p>	USPAT; US-PGPUB	2004/09/27 13:43
27	3069	"over etch\$"	USPAT; US-PGPUB	2004/09/27 14:42
28	411	"main etch\$"	USPAT; US-PGPUB	2004/09/27 14:42

29	619	<p> ((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$)))) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$))) or (((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$) ) or "main etch\$" </p>	USPAT; US-PGPUB	2004/09/27 13:46
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30	226	<p>(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$)))) or (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$)) or (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$) )</p>	USPAT; US-PGPUB	2004/09/27 13:46
31	24	<p>(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ("over etch\$" or "main etch\$")</p>	USPAT; US-PGPUB	2004/09/27 13:46

32	238	<p> ((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$)))) or (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$)) or (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$) ) ) or (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ("over etch\$" or "main etch\$")) </p>	USPAT; US-PGPUB	2004/09/27 13:47
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33	124	<p>(((((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (((1st or first or (etch\$ or patern\$ or remov\$) st) with step) with (etch\$ or patern\$ or remov\$)) same (((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with step) with (etch\$ or patern\$ or remov\$)))) or ((((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ((dual or two) with step with (etch\$ or patern\$ or remov\$)))) or ((((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same (oe or me or overetch\$) ) ) or ((((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) same ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") same (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) same (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) same ((oe or me or overetch\$ or (over with etch\$) or (main with etch\$) ) or ("o.e." or "m.e.") or (((1st or first or (etch\$ or patern\$ or remov\$) st) with (etch\$ or patern\$ or remov\$)) same ((2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second) with (etch\$ or patern\$ or remov\$)))) same ("over etch\$" or "main etch\$")))) same (cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide))</p>	USPAT; US-PGPUB	2004/09/27 14:36
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35	1618021	etch\$ or patern\$ or remov\$	JPO; DERWENT	2004/09/27 14:39
36	310091	poly or polysi or polysilicon or polycrystal\$	JPO; DERWENT	2004/09/27 14:39
37	335603	"o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3"	JPO; DERWENT	2004/09/27 14:39
38	757669	oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide	JPO; DERWENT	2004/09/27 14:39
39	266706	plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion)	JPO; DERWENT	2004/09/27 14:40
40	0	"o.e." or "m.e."	JPO; DERWENT	2004/09/27 14:40
41	2050890	1st or first or (etch\$ or patern\$ or remov\$) st	JPO; DERWENT	2004/09/27 14:41
42	1876300	2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second	JPO; DERWENT	2004/09/27 14:41
43	279414	cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide)	JPO; DERWENT	2004/09/27 14:42
44	308	"over etch\$"	JPO; DERWENT	2004/09/27 14:42
45	64	"main etch\$"	JPO; DERWENT	2004/09/27 14:42
46	92628	oe or me or overetch\$ or (over with etch\$) or (main with etch\$)	JPO; DERWENT	2004/09/27 14:46
47	1641	(etch\$ or patern\$ or remov\$) with (dual or two) with step	JPO; DERWENT	2004/09/27 14:43
48	23424	(etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)	JPO; DERWENT	2004/09/27 14:44
49	229	((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))	JPO; DERWENT	2004/09/27 14:44
50	90800	(etch\$ or patern\$ or remov\$) with (1st or first or (etch\$ or patern\$ or remov\$) st)	JPO; DERWENT	2004/09/27 14:44
51	82237	(etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second)	JPO; DERWENT	2004/09/27 14:45
52	61188	((etch\$ or patern\$ or remov\$) with (1st or first or (etch\$ or patern\$ or remov\$) st)) and ((etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second))	JPO; DERWENT	2004/09/27 14:45
53	27	((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) and (((etch\$ or patern\$ or remov\$) with (dual or two) with step) or (((etch\$ or patern\$ or remov\$) with (1st or first or (etch\$ or patern\$ or remov\$) st)) and ((etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second))))	JPO; DERWENT	2004/09/27 14:45
54	78436	oe or me or overetch\$ or "over etch\$" or "main etch\$"	JPO; DERWENT	2004/09/27 14:46
55	7	((((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) and (oe or me or overetch\$ or "over etch\$" or "main etch\$"))	JPO; DERWENT	2004/09/27 14:47

56	53	(cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide)) and (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion)))	JPO; DERWENT	2004/09/27 14:47
57	80	(((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) and (((etch\$ or patern\$ or remov\$) with (dual or two) with step) or (((etch\$ or patern\$ or remov\$) with (1st or first or (etch\$ or patern\$ or remov\$) st)) and ((etch\$ or patern\$ or remov\$) with (2nd or (poly or polysi or polysilicon or polycrystal\$) nd or second)))) or (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))) and (oe or me or overetch\$ or "over etch\$" or "main etch\$")) or ((cl or "cl2" or "cl.sub.2" or hbr or chlorine or hydrobromic or (hydro with bromic) or (hydrogen with bromide)) and (((etch\$ or patern\$ or remov\$) with (poly or polysi or polysilicon or polycrystal\$)) and ("o2" or oxygen or "o.sub.2" or "o3" or ozone or "o.sub.3") and (oxide or sio or "sio2" or "sio.sub.2" or dioxide or monoxide) and (plasma or sputter\$ or corona or rie or mrie or merie or (glow with discharg\$) or (reactive with ion))))	JPO; DERWENT	2004/09/27 14:47